

	Hits	Search Text	DBs
18	0	((photoresist or resist) same ((upper or top or second) near9 (coat\$4 or film or layer)) same ((lower or bottom or first) near9 (coat\$4 or film or layer)) same (expos\$4 or illuminat\$4 or irradiat\$4) same (substrate or workpiece or device)) and (reticle or photomask or mask or (phase near9 mask)) and (dual near6 damascene) and (half\$4tone same (phase near3 shift) same degree)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB
19	0	((photoresist or resist) same ((upper or top or second) near9 (coat\$4 or film or layer)) same ((lower or bottom or first or under or underlying) near9 (coat\$4 or film or layer or deposit\$4 or substrate)) same (expos\$4 or illuminat\$4 or irradiat\$4) same (substrate or workpiece or device)) and (reticle or photomask or mask or (phase near9 mask)) and (dual near6 damascene) and (half\$4tone same (phase near3 shift\$4) same degree)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB

	Hits	Search Text	DBs
20	18	((photoresist or resist) same ((upper or top or two or second or double) near9 (coat\$4 or film or layer)) same ((lower or bottom or first) near9 (coat\$4 or film or layer)) same (expos\$4 or illuminat\$4 or irradiat\$4) same (substrate or workpiece or device)) and ((reticle or photomask or (phase\$3 near4 shift\$4 near4 mask) or mask) same ((partial\$4 or semi\$3) near8 (absorb\$4 or transmit\$5 or transparen\$2 or opaque or block\$5)) same (attenuat\$4 or (phase near5 shift\$4))) and (((opaque or chrome) near6 (film or layer or coat\$4)) same (PSM or (phase\$4shift\$4 near5 mask) or mask or reticle or photomask)) and (half\$4tone same (phase near3 shift\$4))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB

	Hits	Search Text	DBs
21	45	((reticle or photomask or (phase\$3 near4 shift\$4 near4 mask) or mask) same ((partial\$4 or semi\$3) near8 (absorb\$4 or transmit\$5 or transparen\$2 or opaque or block\$5)) same (attenuat\$4 or (phase near5 shift\$4))) and (((opaque or chrome) near6 (film or layer or coat\$4)) same (PSM or (phase\$4shift\$4 near5 mask) or mask or reticle or photomask)) and (half\$4tone same (phase near3 shift\$4)) and ((dielectric or substrate or photoresist or resist or opaque or insulat\$4) same etch\$4 same (first or second or rate))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB